

consisting of a porous layer is formed on the surface of the aluminum electrode.

Please replace the paragraph beginning at page 15, line 4 with the following rewritten paragraph:

When expressed in the form of a typical view, the porous layer produced on the surface of the aluminum electrode, light reflecting film 16, is arranged such that fine holes, oxide cells each surrounding this fine hole and barrier layers each constituting the bottom portion of the fine hole are successively formed in large number. Accordingly, the configuration of the porous layer can be changed by varying the conditions of the anodization treatment. -

Please add claims 31-34.

-- 31. (New) A reflection type liquid crystal display device comprising:
at least one thin film transistor formed over an active matrix substrate;
a pixel electrode connected to said thin film transistor;
an insulating film formed between said thin film transistor and said pixel electrode; and

a light reflective film formed on said pixel electrode,
wherein said light reflective film has a porous surface, and has
concavities and convexities.

32. (New) A liquid crystal display device of claim 31,
wherein said light reflective film comprises an oxide film.

33. (New) A liquid crystal display device of claim 31,
wherein said insulating film comprises at least one selected
from the group consisting of silicon oxide, silicon nitride, and
an organic resin.

34. (New) A liquid crystal display device of claim 31
further comprising at least one driving thin film transistor
formed over said active matrix substrate for driving said thin
film transistors connected to said pixel electrodes. --